

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination FORESTER, LYNN	
		Examiner Andrew O. Arena	Art Unit 2811	Page 1 of 1

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	C	US-			
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	M	US-			

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NON-PATENT DOCUMENTS

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.